Wolfspeed SiC and GaN Materials













MANAGEMENT



Industry-Leading Portfolio, Innovation and Scale

UNPRECEDENTED PERFORMANCE & SCALE

With more than 30 years of development and manufacturing experience, Wolfspeed is driving innovation with the industry's broadest range of SiC and GaN materials. Delivering substrate and epitaxy options up to 150mm diameter, Wolfspeed provides a vertically integrated materials product offering that combines industry-leading volume, scale, quality and a vast intellectual property portfolio.

When you partner with Wolfspeed, you get the best and most innovative materials.

MATERIALS PORTFOLIO

Supported DiametersSiC SubstratesSiC EpitaxyGaN Epitaxy• 100 mm• n-type• n-type• GaN, AlN, AlGaN• 150 mm• High Purity Sl• p-type• AlInN, SiN layers• Thick epitaxy• HEMT structures

Learn how Wolfspeed can revolutionize your designs at **wolfspeed.com/materials** or contact us at materials_sales@wolfspeed.com or +1.919.313.5300.



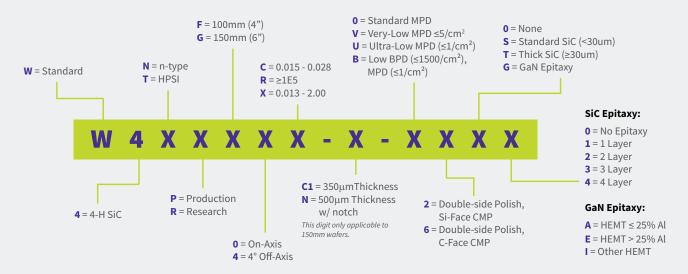
N-TYPE SIC SUBSTRATE PRODUCT DESCRIPTIONS

Part Number	Description
W4NRF4C-V200	4H-SiC, n-type, Research Grade, 100mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Very Low MPD ≤5/cm2, 350um Thick w/ 32.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NPF4C-V200	4H-SiC, n-type, Production Grade, 100mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Very Low MPD ≤5/cm2, 350um Thick w/ 32.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NRF4C-U200	4H-SiC, n-type, Research Grade, 100mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Ultra Low MPD ≤1/cm2, 350um Thick w/ 32.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NPF4C-U200	4H-SiC, n-type, Production Grade, 100mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Ultra Low MPD ≤1/cm2, 350um Thick, w/ 32.5mm Flat Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NPF4C-B200	4H-SiC, n-type, Production Grade, 100mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Ultra Low MPD ≤1/cm2, Low BPD ≤1500/cm2, 350um Thick w/ 32.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NRG4C-C1-V200	4H-SiC, n-type, Research Grade, 150mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Very Low MPD ≤5/cm2, 350um Thick w/ 47.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NPG4C-C1-V200	4H-SiC, n-type, Production Grade, 150mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Very Low MPD ≤5/cm2, 350um Thick w/ 47.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NRG4C-C1-U200	4H-SiC, n-type, Research Grade, 150mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Ultra Low MPD ≤1/cm2, 350um Thick w/ 47.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NPG4C-C1-U200	4H-SiC, n-type, Production Grade, 150mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Ultra Low MPD ≤1/cm2, 350um Thick w/ 47.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4NPG4C-C1-B200	4H-SiC, n-type, Production Grade, 150mm, 4° Off-Axis, 0.015-0.028 ohm-cm, Ultra Low MPD ≤1/cm2, Low BPD ≤1500/cm2, 350um Thick w/ 47.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate

HIGH PURITY SEMI-INSULATING SIC SUBSTRATE PRODUCT DESCRIPTIONS

Part Number	Description
W4TRF0R-0200	4H-SiC, HPSI, Research Grade, 100mm, On-Axis, ≥1E5 ohm-cm, Standard MPD, 500um Thick w/32.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4TPF0R-0200	4H-SiC, HPSI, Production Grade, 100mm, On-Axis, ≥1E5 ohm-cm, Standard MPD, 500um Thick w/ 32.5mm Flat, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4TRG0R-N-0200	4H-SiC, HPSI, Research Grade, 150mm, On-Axis, ≥1E5 ohm-cm, Standard MPD, 500um Thick w/ Notch, Double-Sided Polish Si Face CMP Epi Ready, Bare Substrate
W4TPG0R-N-0200	4H-SiC, HPSI, Production Grade, 150mm, On-Axis, ≥1E5 ohm-cm, Standard MPD, 500um Thick w/ Notch, Double- Sided Polish Si Face CMP Epi Ready, Bare Substrate

How to Order



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